PROCEEDINGS OF SPIE

Semiconductor Lasers and Applications IX

Ning Hua Zhu Werner H. Hofmann Jian-Jun He Editors

21–23 October 2019 Hangzhou, China

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Published by SPIE

Volume 11182

Proceedings of SPIE 0277-786X, V. 11182

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Semiconductor Lasers and Applications IX, edited by Ning Hua Zhu, Werner H. Hofmann, Jian-Jun He, Proc. of SPIE Vol. 11182, 1118201 · © 2019 SPIE CCC code: 0277-786X/19/\$21 · doi: 10.1117/12.2560383 The papers in this volume were part of the technical conference cited on the cover and title page. Papers were selected and subject to review by the editors and conference program committee. Some conference presentations may not be available for publication. Additional papers and presentation recordings may be available online in the SPIE Digital Library at SPIEDigitalLibrary.org.

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Please use the following format to cite material from these proceedings:

Author(s), "Title of Paper," in Semiconductor Lasers and Applications IX, edited by Ning Hua Zhu, Werner H. Hofmann, Jian-Jun He, Proceedings of SPIE Vol. 11182 (SPIE, Bellingham, WA, 2019) Sevendigit Article CID Number.

ISSN: 0277-786X ISSN: 1996-756X (electronic)

ISBN: 9781510630819 ISBN: 9781510630826 (electronic)

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